

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Smith et al.

Docket No.: TI-29811

Serial No: TBD

Examiner: TBD

Filed: 10/11/01

Art Unit: TBD

For: HYDROGEN PLASMA PHOTORESIST STRIP AND POLYMERIC  
RESIDUE CLEANUP PROCESS FOR LOW DIELECTRIC CONSTANT  
MATERIALS

PRELIMINARY AMENDMENT

October 11, 2001

Assistant Commissioner for Patents

Washington, DC 20231

Dear Sir:

Please amend the above referenced application as follows:

In the Specification:

Page 1, before line 1, insert --This application claims priority under 35 USC §  
119(e)(1) of provisional application numbers **60/248,996** filed **11/15/00**--